

# INFORMATION DISCLOSURE STATEMENT BY APPLICANT

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Application Number	10/528,376
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First Named Inventor	Masamichi MORITA
Art Unit	1794
Examiner Name	Gerard T. Higgins
Attorney Docket Number	Q86778

## U.S. PATENTS

Examiner Initials*	Cite No	Patent Number	Kind Code <sup>1</sup>	Issue Date	Name of Patentee or Applicant of cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
1						

## U.S. PATENT APPLICATION PUBLICATIONS

Examiner Initials*	Cite No	Publication Number	Kind Code <sup>1</sup>	Publication Date	Name of Patentee or Applicant of cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
1	20020081520	A1	2002-06-27	SOORIYAKUMARAN et al.		

## FOREIGN PATENT DOCUMENTS

Examiner Initials*	Cite No	Foreign Document Number <sup>2</sup>	Country Code <sup>2</sup>	Kind Code <sup>4</sup>	Publication Date	Name of Patentee or Applicant of cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	T <sup>5</sup>
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## NON-PATENT LITERATURE DOCUMENTS

Examiner Initials*	Cite No	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city, and/or country where published.	T <sup>4</sup>
1	H. SUGIMURA, et al.; "Micropatterning of Alkyl- and Fluoroalkylsilane Self-Assembled Monolayers Using Vacuum Ultraviolet Light"; Langmuir; Vol. 16, No. 3; 2000; pp. 885-888		
2	Noo LI JEON, et al.; "Patterned Self-Assembled Monolayers Formed by Microcontact Printing Direct Selective Metalization by Chemical Vapor Deposition on Planar and Nonplanar Substrates"; Langmuir; Vol. 11, No. 8; 1995; pp. 3024-3026		
3	Noo LI JEON, et al.; "A Monolayer-Based Lift-Off Process for Patterning Chemical Vapor Deposition Copper Thin Films"; Langmuir; Vol. 12, No. 22; 1996; pp. 5350-5355		
4	Peter C. RIEKE, et al.; "Spatially Resolved Mineral Deposition on Patterned Self-Assembled Monolayers"; Langmuir; Vol. 10, No. 3; 1994; pp. 619-622		
5	Patrick W. HOFFMAN, et al.; "Vapor Phase Self-Assembly of Fluorinated Monolayers on Silicon and Germanium Oxide"; Langmuir; Vol. 13, No. 7; 1997; pp. 1877-1880		
6	Pamela M. ST. JOHN, et al.; "Monolayers of fluorinated silanes as electron-beam resists"; Journal of Vacuum Science & Technology: Part B; Vol. 14, No. 1; Jan/Feb 1996; pp. 69-74		
7	Rochael J. COLLINS, et al.; "Low temperature deposition of patterned TiO <sub>2</sub> thin films using photopatterned self-assembled monolayers"; Applied Physics Letters; Vol. 69, No. 6; 5 August 1996; pp. 860-862		

## EXAMINER SIGNATURE

Examiner Signature	/Gerard Higgins/	Date Considered	02/11/2009
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ALL REFERENCES CONSIDERED EXCEPT WHERE LINED THROUGH. /G.H./